

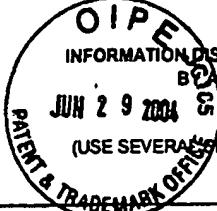
FORM PTO-1449 INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(USE SEVERAL SHEETS IF NECESSARY)</i>	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. ASMEX 378A	APPLICATION NO. 10/623,482
		APPLICANT Todd et al.	
		FILING DATE July 18, 2003	GROUP 2812

APR 19 2004

U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
RJ	1 5,389,570	2/14/95	Shiozawa			
2						
3						
4						
5						

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EXAMINER <i>Tom Pompey</i>	DATE CONSIDERED <i>6-8-05</i>
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. ASMX376A	APPLICATION NO. 10/623,482
 INFORMATION DISCLOSURE STATEMENT BY APPLICANT JUN 29 2004 (USE SEVERAL SHEETS IF NECESSARY)		APPLICANT Todd et al.	
		FILING DATE July 18, 2003	GROUP 2812

U.S. PATENT DOCUMENTS						
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS
R.P	1	6,391,803 B1	5/21/02	Kim et al.		
R.P	2	6,468,924 B2	10/22/02	Lee et al.		
R.P	3	6,528,530 B2	3/4/03	Zeitlin et al.		
R.P	4	6,638,879 B2	10/28/03	Hsich et al.		
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EXAMINER <i>Ron Pompey</i>	DATE CONSIDERED <i>6-8-05</i>
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<p style="text-align: center;">OIPS AUG 26 2006 U.S. DEPARTMENT OF COMMERCE PATENT & TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT (USE SEVERAL SHEETS IF NECESSARY)</p>	ATTY. DOCKET NO. ASMEX378A	APPLICATION NO. 10/623,482
	APPLICANT Todd et al.	
	FILING DATE July 18, 2003	GROUP 2812

U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
RP	1. 5,389,570	2/14/95	Shiozawa			

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EXAMINER <i>Tom Foley</i>	DATE CONSIDERED <i>6-8-05</i>
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	

INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application No.	10/623482
	Filing Date	July 18, 2003
	First Named Inventor	Michael A. Todd et al.
	Art Unit	2812
<i>(Multiple sheets used when necessary)</i>	Examiner	Unknown
SHEET 1 OF 1	Attorney Docket No.	ASMEX.376A

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

RELEVANT FOREIGN DOCUMENTS					
Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear

NON PATENT LITERATURE DOCUMENTS

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032205

***Examiner:** Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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T¹ - Place a check mark in this area when an English language Translation is attached.

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Multiple sheets used when necessary)

SHEET 1 OF 1

Application No.	10/623482
Filing Date	July 18, 2003
First Named Inventor	Michael A. Todd et al.
Art Unit	2812
Examiner	Unknown
Attorney Docket No.	ASMEX.376A

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

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Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear
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NON-PATENT LITERATURE DOCUMENTS

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Examiner Signature Ron Pompey Date Considered 6-8-05

***Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.**

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FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. ASMEX.378A	APPLICATION NO. 10/623,482
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT Todd et al.	
(USE SEVERAL SHEETS IF NECESSARY)		FILING DATE July 18, 2003	GROUP 2812
 NOV 17 2003 22		U.S. PATENT DOCUMENTS	

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
RP	4,262,631	4/21/81	Kubacki			
RP	4,277,320	7/7/81	Beguwala et al.			
RP	4,298,629	11/3/81	Nozaki et al.			
RP	4,363,828	12/14/82	Brodsky et al.			
RP	4,495,218	1/22/85	Azuma et al.			
RP	4,585,671	4/29/86	Kitagawa et al.			
RP	4,684,542	8/4/87	Jasinski et al.			
RP	4,715,937	12/29/87	Mosleh et al.			
RP	5,227,329	7/13/93	Kobayashi et al.			
RP	5,389,398	02/14/95	Suzuki et al.	427	130	
RP	5,607,724	3/4/97	Beinglass et al.			
RP	5,614,257	3/25/97	Beinglass et al.			
RP	5,648,293	7/15/97	Hayama et al.			
RP	5,656,531	8/12/97	Thakur et al.			
RP	5,695,819	12/9/97	Beinglass et al.			
RP	5,698,771	12/16/97	Shields et al.	73	31.05	
RP	5,700,520	12/23/97	Beinglass et al.			
RP	5,786,027	7/28/98	Rolfson			
RP	5,789,030	8/4/98	Rolfson			
RP	5,837,580	11/17/98	Thakur et al.			
RP	5,874,129	2/23/99	Beinglass et al.			
RP	5,876,797	3/2/99	Beinglass et al.			
RP	5,885,869	3/23/99	Turner et al.			
RP	5,907,792	5/25/99	Droopad et al.			
RP	6,027,705	2/22/00	Kitsuno et al.			11/30/98
RP	6,083,810	7/4/00	Obeng et al.			12/5/96

EXAMINER	<i>Ron Pompey</i>	DATE CONSIDERED	<i>6-8-05</i>
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>IPR</i> USE SEVERAL SHEETS IF NECESSARY <i>JULY 17 2003</i>		APPLICANT Todd et al.	
		FILING DATE July 18, 2003	GROUP 2812

U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
RJ	27. 6,136,654	10/24/00	Kraft et al.			
RP	28. 6,159,828	12/12/00	Ping et al.	438	486	
RP	29. 6,171,662 B1	01/09/01	Nakao	427	595	
RP	30. 6,197,669 B1	03/06/01	Twu et al.	438	585	
RP	31. 6,197,694 B1	3/6/01	Beinglass			7/31/96
RP	32. 6,228,181	05/08/01	Yamamoto et al.	148	33.5	
RP	33. 6,326,311	12/04/01	Ueda et al.	438	694	
RP	34. 6,455,892	09/24/02	Okuno et al.	257	328	
RP	35. 6,537,910 B1	3/25/03	Burke et al.			
RP	36. 6,613,695	09/02/03	Pomaredo et al.	438	767	
RP	37. US 2002/0098627 A1	07/25/02	Pomaredo et al.	438	149	08/31/01
RP	38. US 2002/0168868 A1	11/14/02	Todd	438	767	2/11/02
RP	39. US 2002/0197831 A1	12/26/02	Todd et al.	438	528	2/11/02
RP	40. US 2003/0022528 A1	1/30/03	Todd	438	933	2/11/02
RP	41. US 2003/0082300 A1	5/1/03	Todd et al.	427	255.27	2/11/02

FOREIGN PATENT DOCUMENTS						
EXAMINE R INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLAS S	SUBCLAS S	TRANSLATION
						YES NO
RP	42. 57209810 A	12/23/82	Japan			Abstract
RP	43. 59078918 A	5/8/84	Japan			Abstract
RP	44. 59078919 A	5/8/84	Japan			Abstract
RP	45. 60043485 A	3/8/85	Japan			Abstract
RP	46. 61153277 A	7/11/86	Japan			Abstract
RP	47. 62076612 A	4/8/87	Japan			Abstract
RP	48. 63003414 A	1/8/88	Japan			Abstract
RP	49. 63003463 A	1/8/88	Japan			Abstract

EXAMINER <i>Ron Longley</i>	DATE CONSIDERED <i>6-80J</i>
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT		NOV 17 2003 JC22 PATENT & TRADEMARK OFFICE	
(USE SEVERAL SHEETS IF NECESSARY)		FILING DATE July 18, 2003	GROUP 2812

FOREIGN PATENT DOCUMENTS								
EXAMINE R INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLAS S	SUBCLAS S	TRANSLATION	
							YES	NO
RP	50.	01217956 A	8/31/89	Japan			Abstract	
RP	51.	01268064 A	10/25/89	Japan			Abstract	
RP	52.	02155225 A	6/14/90	Japan			Abstract	
RP	53.	03091239 A	4/16/91	Japan			Abstract	
RP	54.	03185817 A	8/13/91	Japan			Abstract	
RP	55.	03187215 A	8/15/91	Japan			Abstract	
RP	56.	03292741 A	12/24/91	Japan			Abstract	
RP	57.	04323834 A	11/13/92	Japan			Abstract	
RP	58.	05021378 A	1/29/93	Japan			Abstract	
RP	59.	05062911 A	3/12/93	Japan			Abstract	
RP	60.	07249618 A	9/26/95	Japan			Abstract	
RP	61.	08242006 A	9/17/96	Japan			Abstract	
RP	62.	S60-43485	3/8/85	Japan (Patent Disclosure)			X	
RP	63.	H 02-155225	6/14/90	Japan (Patent Disclosure)			X	
RP	64.	H3-185817	8/13/91	Japan (Patent Disclosure)			X	
RP	65.	H3-187215	8/15/91	Japan (Patent Disclosure)			X	
RP	66.	H3-91239	4/16/91	Japan (Patent Disclosure)			X	
RP	67.	H5-62911	3/12/93	Japan (Patent Disclosure)			X	

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)	
RP	68	Ikoma et al., Growth of Si/3C-SiC/Si(100) heterostructures by pulsed supersonic free jets, Applied Physics Letters, Volume 75, No. 25, Pp. 3977-3979, December 1999
	69	
	70	

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EXAMINER <i>Ron Pompey</i>	DATE CONSIDERED 6-8-05
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FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. ASMX.376A	APPLICATION NO. Unknown
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT Todd et al.	
(USE SEVERAL SHEETS IF NECESSARY)		FILING DATE Herewith	GROUP Unknown

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
RP	1	4,851,095	7/25/89	Scobey et al.			
RP	2	5,916,365	6/29/99	Sherman			
RP	3	6,015,590	1/18/00	Suntola et al.			
RP	4	6,159,828	12/12/00	Ping et al.			
RP	5	6,200,893 B1	3/13/01	Sneh			

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)
RP	6 Iyer, R. Suryanarayanan et al., "A process Method of Silicon Nitride Atomic Layer Cyclic Deposition," Semicon Taiwan 2001, pp. 17-25
	7
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EXAMINER	<i>Lam Pompey</i>	DATE CONSIDERED	<i>6-8-05</i>
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